AMENDMENTS TO THE CLAIMS:

Please cancel Claims 10 through 65 without prejudice of disclaimer of subject matter.

Please amend Claims 1 and 5 and add Claim 66 as follows:

1. (Currently Amended) A substrate processing apparatus comprising:

an alignment system disposed at a position such that information regarding a pattern arrangement of a substrate is obtained;

a processing system disposed separately from the alignment system and used for processing a substrate;

a first substrate stage which is able to support a substrate and move in an xy plane, the xy plane being a plane parallel to a direction of an arrangement between the alignment system and the processing system and a z axis being an axis perpendicular to the xy plane;

a second substrate stage which is able to support a substrate and move in the xy plane; and

~~position measurement systems, each of which measures positions of the first and second substrate stages,~~

~~wherein at least three position measurement systems are arranged for the position measurement in the x direction of the first stage and the second stage during movement of the first and second stages between the processing system position and the alignment system position and at least three position measurement systems are arranged for the position measurement in the y~~

~~direction of the first stage and the second stage during movement of the first and second stages between the processing system position and the alignment system position, at least one of the position measurement systems for the position measurement in the y direction being disposed at an opposite side of another one of the position measurement systems for the position measurement in the y direction~~

at least three x-position measurement systems, each of which measures positions of the first and second substrate stages during movement between the processing system position and the alignment system position;

at least three y-position measurement systems, each of which measures positions and rotations of the first and second substrate stages during movement between the processing system position and the alignment system position,

wherein at least one of the y-position measurement systems is disposed at an opposite side of another one of the y-position measurement systems.

2. (Original) An apparatus according to Claim 1, wherein a position measurement operation of a substrate in the alignment system, the substrate being supported by one of the first and second substrate stages, and a processing operation of a substrate in the processing system, the substrate being supported by the other one of the first and second substrate stages, are performed in parallel.

3. (Original) An apparatus according to Claim 1, wherein, every time the first and second substrate stages are aligned in the x direction, the order in which the first and second substrate stages are aligned is the same.

4. (Original) An apparatus according to Claim 1, wherein, when the first and second substrate stages move between the alignment system and the processing system, clockwise and counterclockwise rotations around the z axis are alternately performed.

5. (Currently Amended) An apparatus according to Claim 1, wherein a plurality of x position measurement systems ~~for the position measurement in the x direction~~ is arranged at each side of the first and second substrate stages.

6. (Original) An apparatus according to Claim 1, further comprising two-dimensional driving means, which drive the first and second substrate stages, and comprise a surface motor.

7. (Original) An apparatus according to Claim 1, further comprising suction force suppliers, each of which supplies a suction force for retaining a substrate, connected to the first and second substrate stages at point-symmetric positions across the first and second substrate stages.

8. (Original) An apparatus according to Claim 1, wherein the apparatus serves as an exposure apparatus and further comprises a display, a network interface, and a computer for executing network software, wherein maintenance information of the exposure apparatus is communicated via a computer network.

9. (Original) An apparatus according to Claim 8, wherein the network software provides, on the display, a user interface for accessing a maintenance database, which is provided by a vendor or a user of the exposure apparatus and connected to a network external to a factory in which the exposure apparatus is installed, so that information is obtained from the maintenance database via the external network.

10-65. (Cancelled)

66. (New) A substrate processing apparatus comprising:

an alignment system disposed at a position such that information regarding a pattern arrangement of a substrate is obtained;

a processing system disposed separately from the alignment system and used for processing a substrate;

first and second stages, each of which is able to support a substrate and move in an xy plane, the xy plane being a plane parallel to a direction of an arrangement between the alignment system and the processing system and a z axis being an axis perpendicular to the xy

plane;

at least three x-position measurement systems, each of which measures positions of first and second stages in the x direction;

at least three y-position measurement systems, each of which measures position and rotation of the first and second stages in the y direction,

wherein at least one of the y-position measurement systems is disposed at an opposite side of another one of the y-position measurement systems.